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Atty. Docket No. 30205/39509 Inventors: Cheol Kyu Bok et al.

Title: "Overcoating Composition for Photoresist and Method for Forming Photoresist Pattern Using the Same"

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INCREASE OF EXPOSURE ENERGY









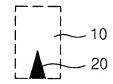


Fig.1 (Prior Art) Atty. Docket No. 30205/39509 Inventors: Cheol Kyu Bok et al.

Title: "Overcoating Composition for Photoresist and Method for Forming Photoresist Pattern Using the Same"

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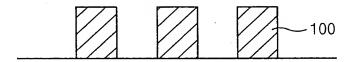


Fig.2a

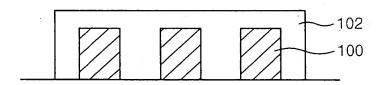


Fig.2b

Atty. Docket No. 30205/39509
Inventors: Cheol Kyu Bok et al.
Title: "Overcoating Composition for Photoresist and

Method for Forming Photoresist Pattern Using the Same"

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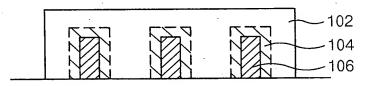


Fig.2c

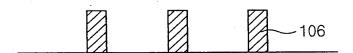


Fig.2d

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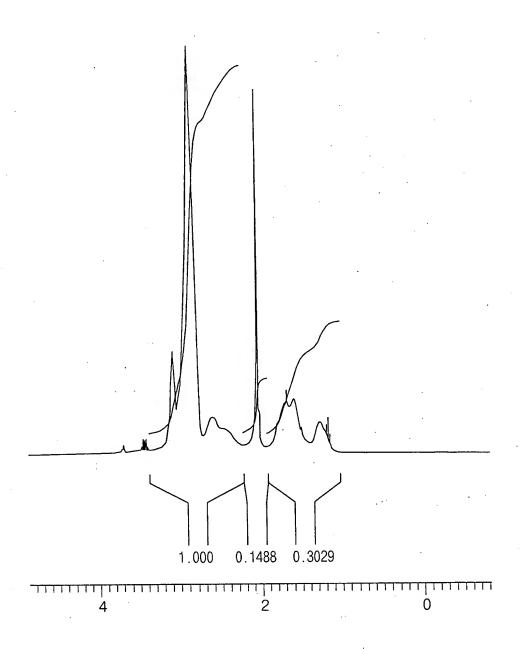


Fig.3

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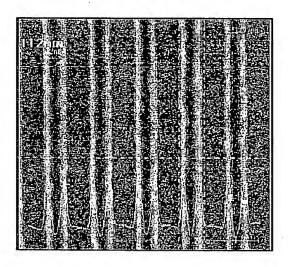


Fig.4a

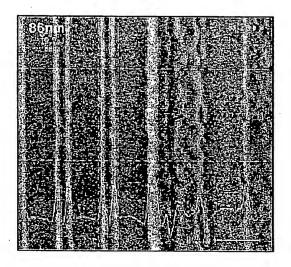


Fig.4b

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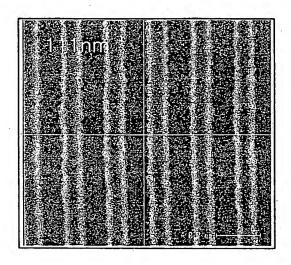


Fig.5a

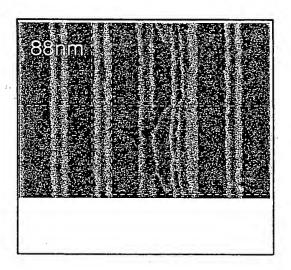


Fig.5b

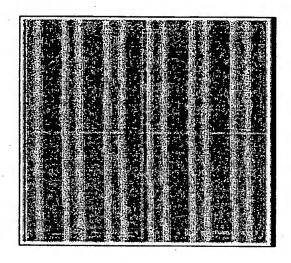


Fig.6a

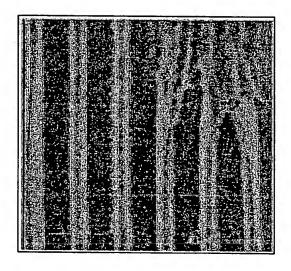


Fig.6b

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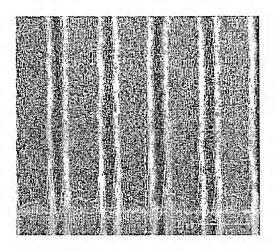


Fig. 7a

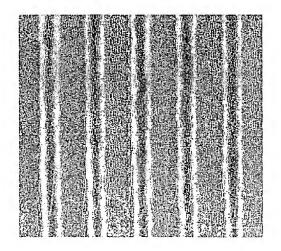


Fig. 7b

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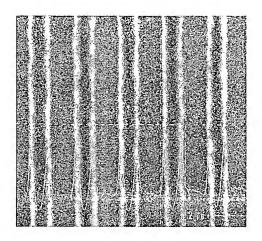


Fig. 8a

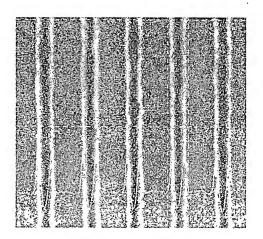


Fig. 8b